

# **Advanced ARPES Analyzer and Momentum Microscope KREIOS 150 – Concepts and first results on layered materials and topological insulators**

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## **Abstract:**

Modern ARPES analyzers provide a high degree of parallelization in data acquisition, recording hundreds of energy and angle channels simultaneously. Additionally, integrated deflectors enable users to perform angle scanning perpendicular to the analyzer's entrance slit to record ( $k_x$ ,  $k_y$ ,  $E$ ) data sets without sample rotation. However, the design of conventional analyzers implies a limited acceptance angle and corresponding accessible momentum space volume. Due to the trade-off between acceptance angle and angle resolution multiple changes in sample position and lens modes are necessary during a typical high resolution ARPES experiment. The new KREIOS 150 Energy Analyzer uses an extractor zoom lens design to overcome these limitations.

This new lens provides a full solid acceptance angle with highest angular resolution. In contrast to standard ARPES measurements with conventional hemispherical analyzers, electronic structure data from and beyond the 1<sup>st</sup> Brillouin zone is recorded without any sample movement. In addition, the lens of such an instrument can work in a lateral imaging mode for microscopy as well. This enables navigation on the sample and reduces the size of the area under investigation in ARPES down to a few micrometers in diameter. This combination of large acceptance angle, high angular resolution, and small acceptance area makes this instrument the ideal tool for electronic structure studies on small samples or sample areas. The design is compact with a straight optical axis.

The capabilities of this instrument were tested at the UE 56/2 at the Bessy II synchrotron in Berlin. Specification tests show excellent angle and lateral resolution as well as small spot capability down to 2 $\mu$ m FOV. Subsequently real live samples like Graphene on Germanium were measured. Even on macroscopically rough surfaces like Graphene on NbSe<sub>2</sub> excellent ARPES and X-PEEM results could be obtained. By taking advantage of the small spot capability of the KREIOS 150 meaningful band structure data has been recorded on such patchy samples.

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